

LISTING OF THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A system ~~System~~ for reducing oxidation of a semiconductor device comprising:

a holding device for securing the semiconductor device to a platform, the holding device including an opening ~~in the holding device for~~ providing access by a bonding tool to an area where the semiconductor device is to be heated;

the holding device further including a cover, the cover defining a hollow cavity located adjacent ~~coupled to the opening; and~~

a gas inlet in fluid communication with the cavity and the opening for supplying a relatively inert gas ~~to the cavity; and~~

the holding device further defining a conduit connecting the gas inlet and hollow cavity, the conduit having a smaller cross-sectional area than the cavity, the conduit for whereby to ~~transmit~~ transmitting the inert gas to the opening through the cavity.

2. (Amended) A system ~~System~~ a claimed in claim 1, wherein the cavity is configured such that the inert gas supplied to the cavity is directed away from an outlet connecting the cavity to the opening.

3. (Canceled)

4. (Canceled)

5. (Canceled)
6. (Amended) A system ~~System~~ as claimed in claim 1, wherein the gas inlet is formed in the holding device.
7. (Amended) A system ~~System~~ as claimed in claim 1, wherein the gas inlet is formed in the platform.
8. (Amended) A system ~~System~~ as claimed in claim 1, wherein including a space is defined between the holding device and the platform for receiving the inert gas from the gas inlet and for distributing the inert gas over a surface of the electronic device.
9. (Amended) A system ~~System~~ as claimed in claim 8, wherein the space is connected to the said opening for distributing an amount of the inert gas directly from the space to the opening.
10. (Amended) A system ~~System~~ as claimed in claim 8, ~~including a~~ wherein the conduit ~~linking links~~ the cavity and the space ~~for channeling and channels~~ an amount of the inert gas from the space to the cavity.
11. (Canceled)
12. (Canceled)
13. (Canceled)
14. (Canceled)
15. (Canceled)
16. (Canceled)